

## Supplementary Information

### **Hollow Heterostructured Cu<sub>1.96</sub>S/NiS Microspheres Coupled with Nitrogen/Sulfur Dual-Doped Carbon Realizing Superior Reaction Kinetics and Sodium Storage**

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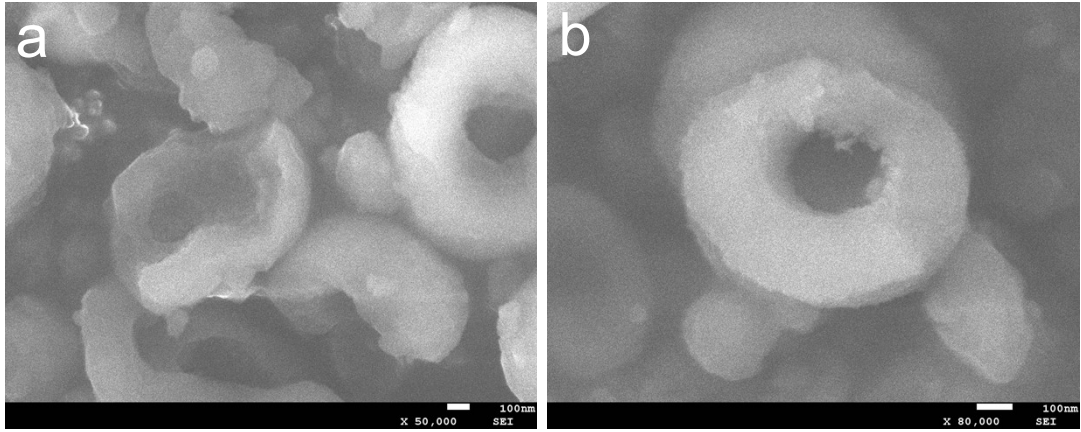


Fig. S1 (a) Low- and (b) high-magnification SEM images of damaged CuNi-G microspheres.

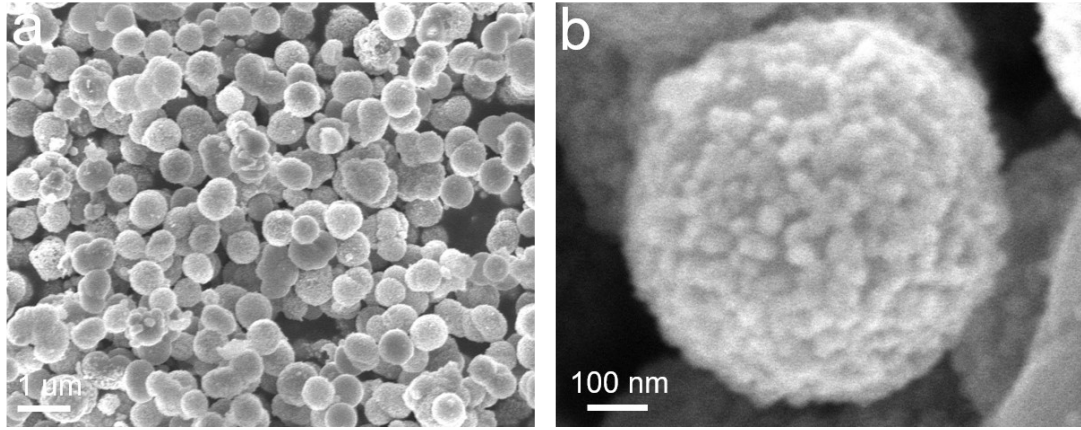


Fig. S2 (a) Low- and (b) high-magnification SEM images of Cu<sub>1.96</sub>S/NiS microspheres.

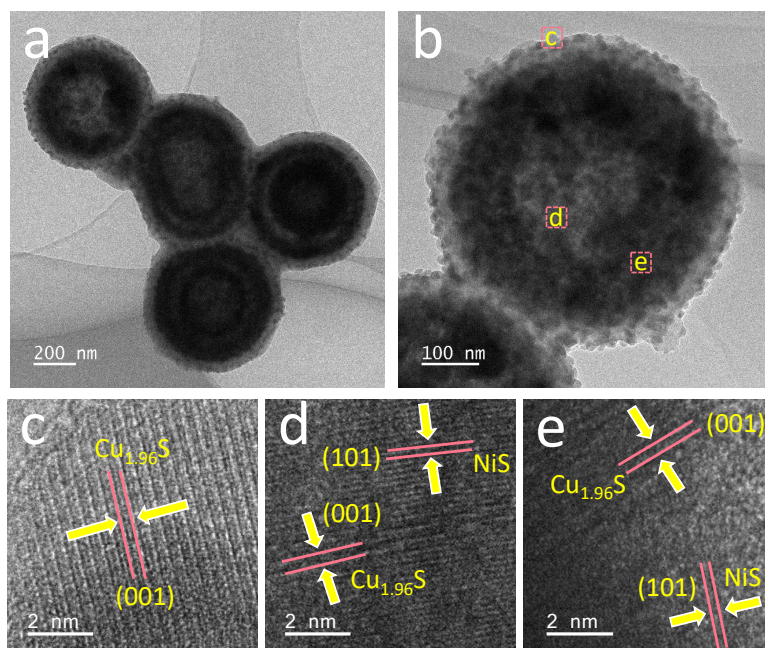


Fig. S3 (a, b) TEM of  $\text{Cu}_{1.96}\text{S}/\text{NiS}@\text{DC}$  microspheres; (c-e) HRTEM images captured from the wall edge of  $\text{Cu}_{1.96}\text{S}/\text{NiS}@\text{DC}$  shown in (b).

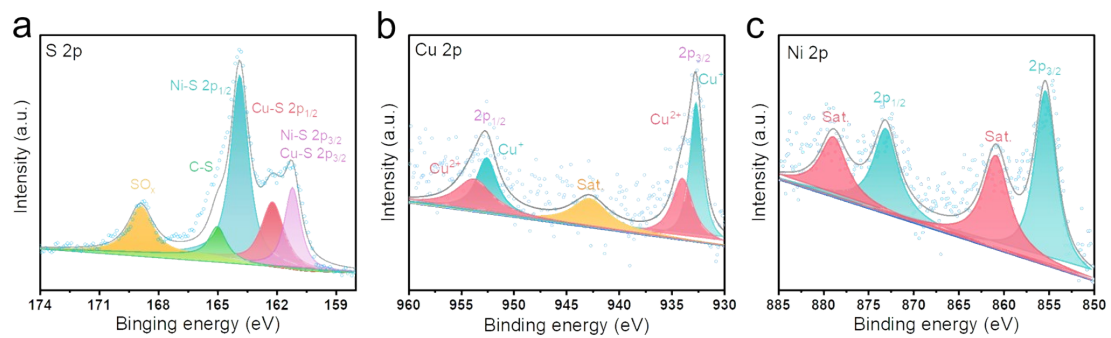


Fig. S4 The high-resolution XPS spectra of (a) S 2p, (b) Cu 2p, and (c) Ni 2p of  $\text{Cu}_{1.96}\text{S}/\text{NiS}$  microspheres.

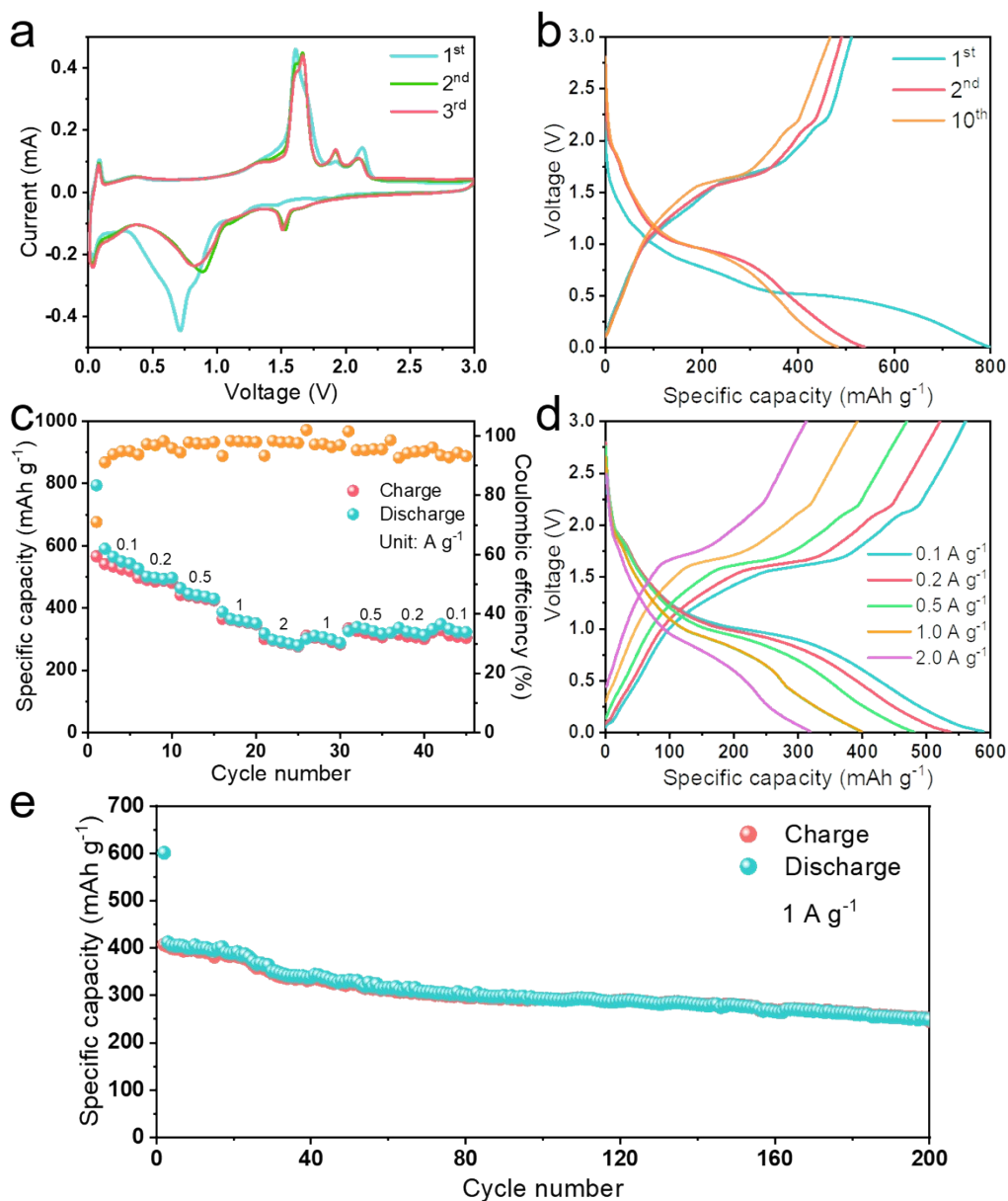


Fig. S5 Electrochemical performance of  $\text{Cu}_{1.96}\text{S}/\text{NiS}$  electrode. (a) CV curves at  $0.1 \text{ mV s}^{-1}$  in the voltage range of 0.01-3.0 V. (b) Galvanostatic charge-discharge voltage profiles at  $0.2 \text{ A g}^{-1}$ . (c) Rate performance and Coulombic efficiency ranging from 0.1 to  $2.0 \text{ A g}^{-1}$ . (d) Voltage profiles at various current densities. (e) Prolonged cycle life and Coulombic efficiency at  $1.0 \text{ A g}^{-1}$ .

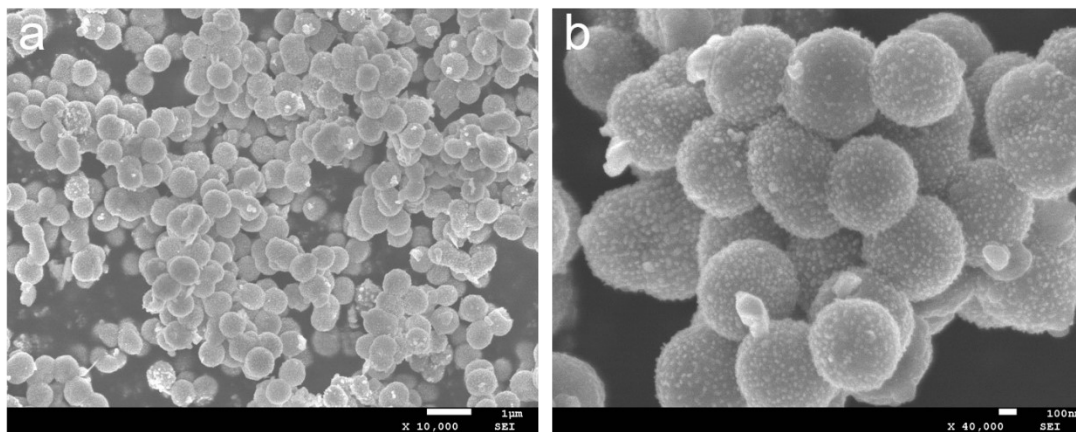


Fig. S6 (a) Low- and (b) high-magnification SEM images of L-Cu<sub>1.96</sub>S/NiS@DC microspheres.

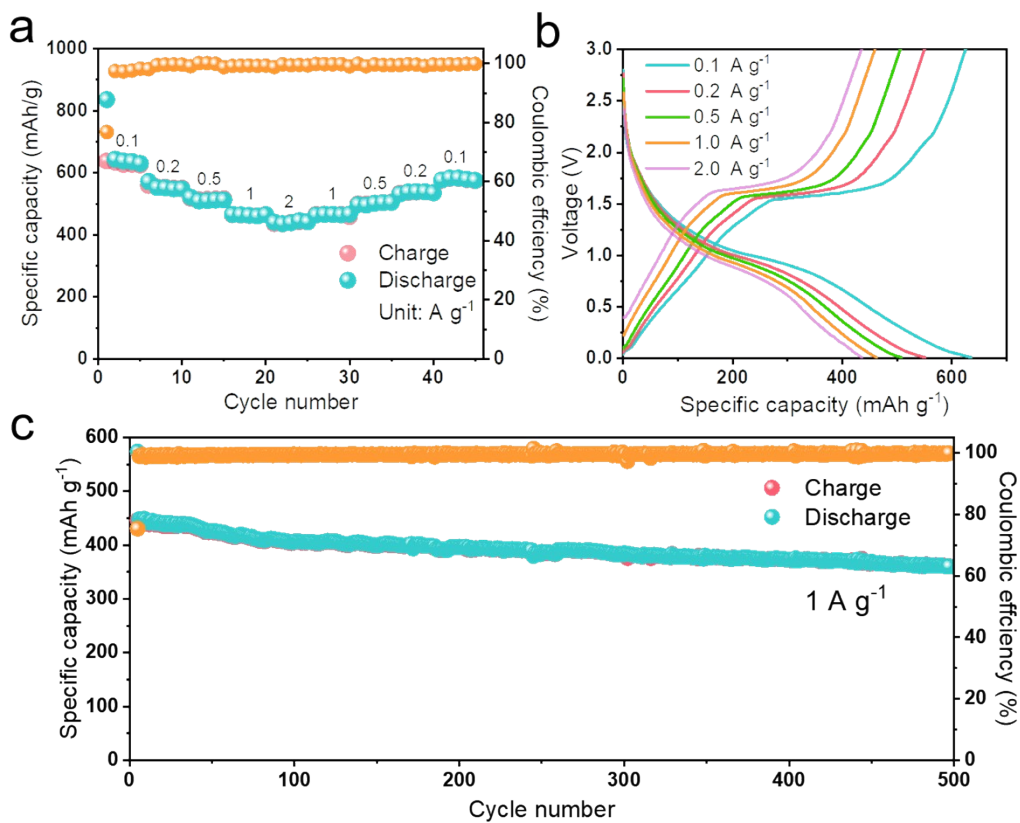


Fig. S7 Electrochemical performance of L-Cu<sub>1.96</sub>S/NiS@DC electrode. (a) Rate performance and Coulombic efficiency ranging from 0.1 to 2.0 A g<sup>-1</sup>. (b) Voltage profiles at various current densities. (c) Prolonged cycle life and Coulombic efficiency at 1.0 A g<sup>-1</sup>.



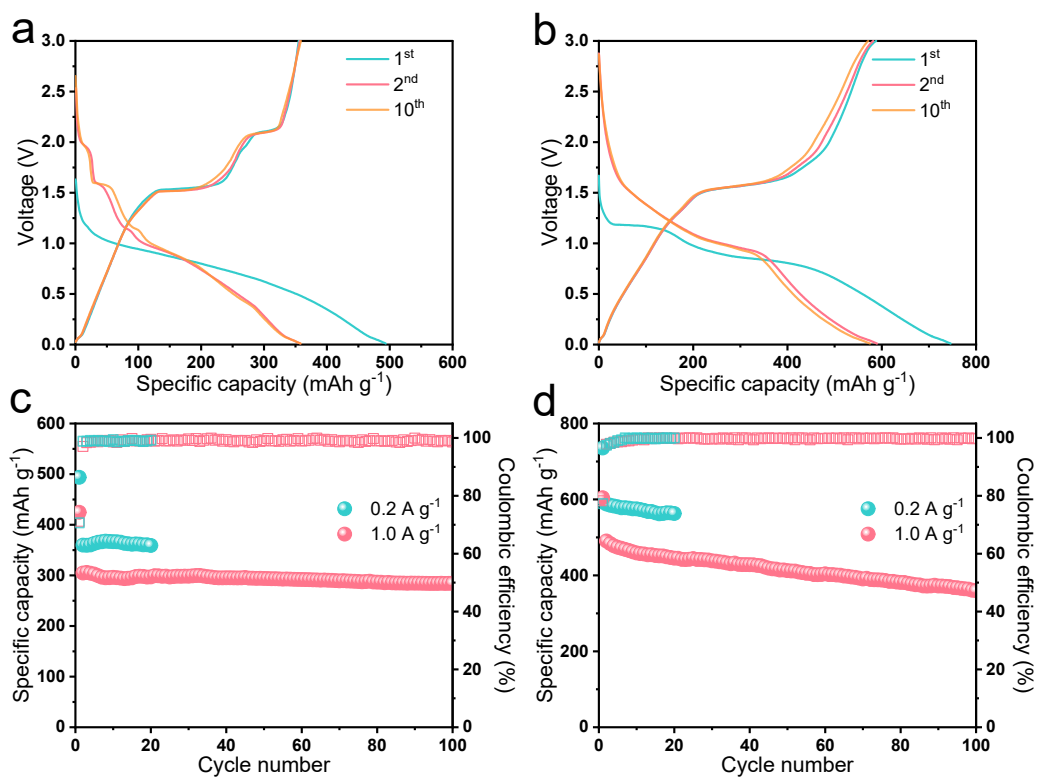


Fig. S8 Galvanostatic charge-discharge voltage profiles of the carbon-coated (a)  $\text{Cu}_{1.96}\text{S}$  and (b) NiS electrodes at  $0.2 \text{ A g}^{-1}$ . Cycle life and Coulombic efficiency of the carbon-coated (c)  $\text{Cu}_{1.96}\text{S}$  and (d) NiS electrodes at  $0.2 \text{ A g}^{-1}$  and  $1.0 \text{ A g}^{-1}$ .

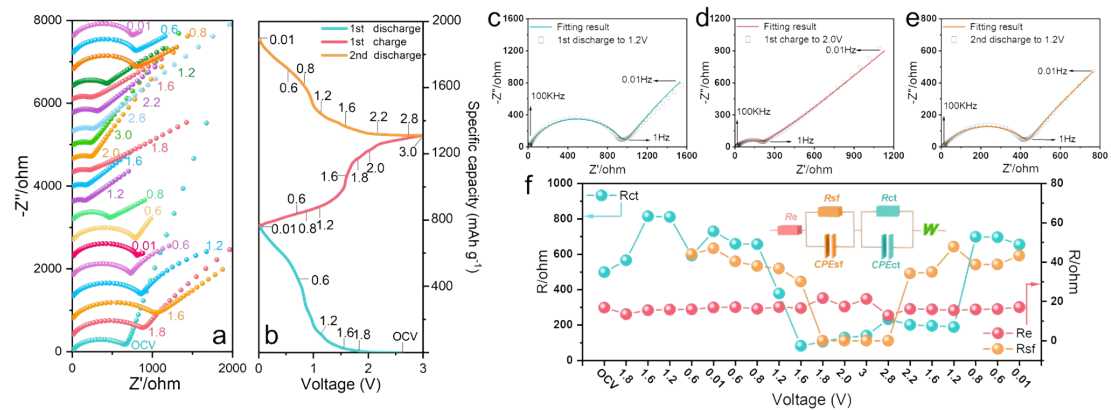


Fig. S9 Electrochemical reaction kinetics of  $\text{Cu}_{1.96}\text{S}/\text{NiS}$  electrode. (a) Nyquist plots collected at each point marked in (b) in the frequency range of 100 kHz to 10 mHz. (b) Discharge-charge profiles: each point represents an EIS measurement. Typical Nyquist plots collected at the (c) 1<sup>st</sup> discharge to 1.2 V, (d) 1<sup>st</sup> charge 2.0 V, and (e) 2<sup>nd</sup> discharge to 1.2 V. (f) EIS parameters derived from the equivalent circuit (inset of f).

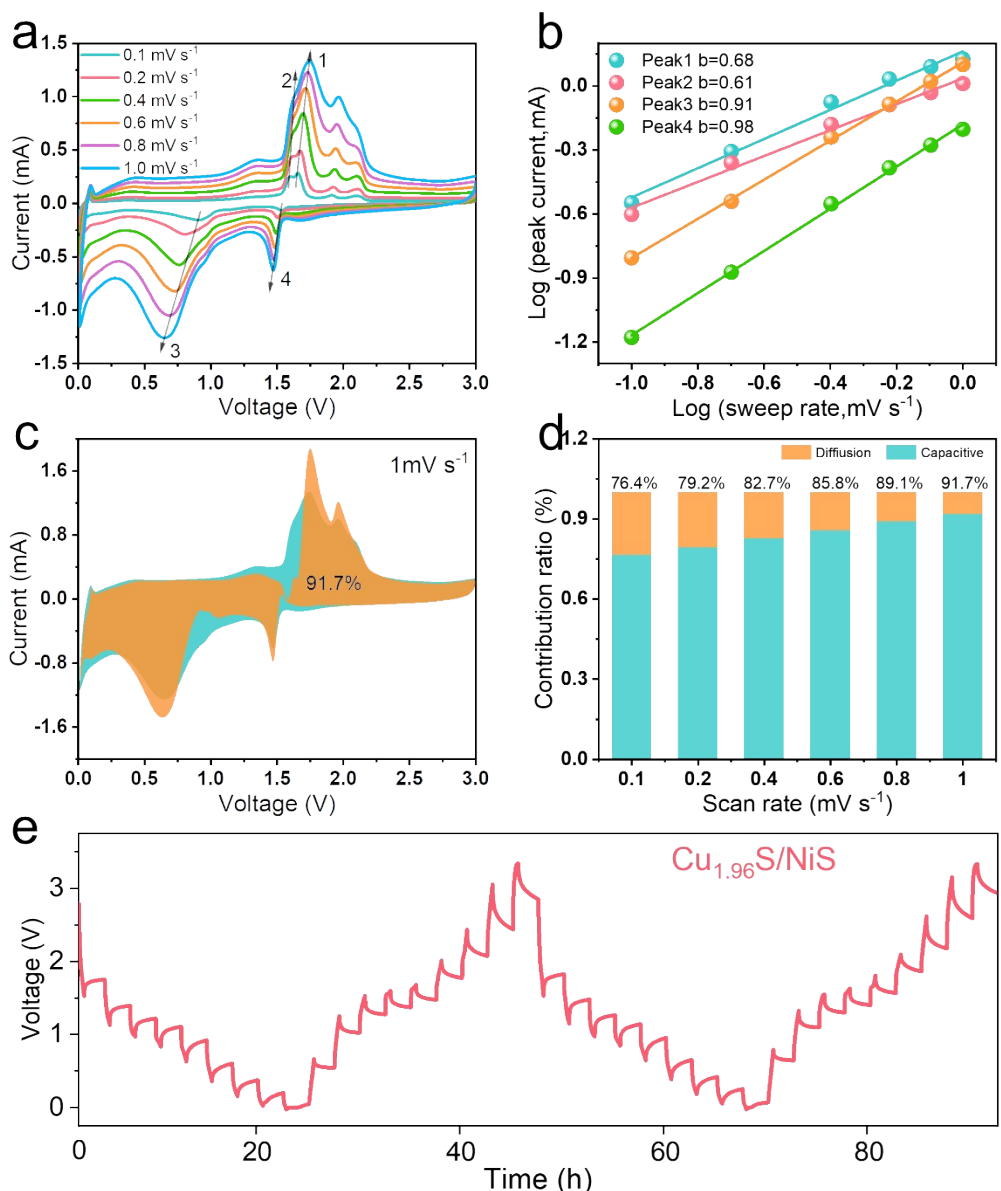


Fig. S10 Electrochemical reaction kinetics of Cu<sub>1.96</sub>S/NiS electrode. (a) CV curves at various scan rates from 0.1 to 1.0 mV s<sup>-1</sup>. (b) Determination of the b value using the relationship between peak current and scan rate. (c) Separation of the capacitive and diffusion currents at a scan rate of 1.0 mV s<sup>-1</sup> with the capacitive fraction shown by the shaded region. (d) Contribution ratio of the capacitive and diffusion-controlled charge versus scan rate. (e) GITT curves.

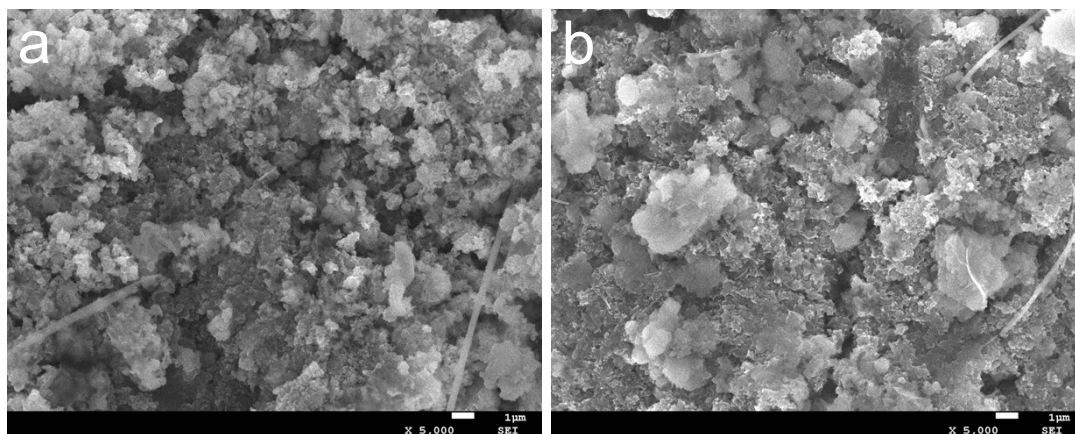


Fig. S11 SEM images of (a) Cu<sub>1.96</sub>S/NiS and (b) Cu<sub>1.96</sub>S/NiS@DC electrodes after 1000 cycles at 1.0 A g<sup>-1</sup>.

Table. S1 The atomic ratio of Cu and Ni in the obtained materials.

	<b>Cu<sub>1.96</sub>S/NiS@DC</b>	<b>L-Cu<sub>1.96</sub>S/NiS@DC</b>
Cu : Ni	0.94 : 1	0.39 : 1

Table S2 Electrochemical performances of Cu<sub>1.96</sub>S/NiS@DC compared with other previously-reported bimetallic sulfides based anode materials for SIBs.

Bimetallic Sulfides	Voltage window [V vs. Na <sup>+</sup> ]	Current density	Capacity retention (%)	Rate capacity (mAh g <sup>-1</sup> ) / current density	Ref.
SnS <sub>2</sub> @MoS <sub>2</sub> @rGO	0.01-3.0	0.1 A g <sup>-1</sup>	92.5 (after 100 cycles)	408 at 0.2 A g <sup>-1</sup> 346 at 0.8 A g <sup>-1</sup>	1
Cu <sub>2</sub> S@ZnS/C	0.4-2.6	0.2 A g <sup>-1</sup>	98.1 (after 200 cycles)	424 at 0.2 A g <sup>-1</sup> 415 at 1 A g <sup>-1</sup>	2
ZnS@NC@MoS <sub>2</sub>	0.01-2.5	1 A g <sup>-1</sup>	81.4 (after 120 cycles)	461.4 at 0.1 A g <sup>-1</sup> 354.6 at 1 A g <sup>-1</sup>	3
NiS/MoS <sub>2</sub> /C	0.01-3.0	1 A g <sup>-1</sup>	70.5 (after 200 cycles)	516 at 0.1 A g <sup>-1</sup> 444 at 1 A g <sup>-1</sup>	4
Ni <sub>3</sub> S <sub>2</sub> /Co <sub>9</sub> S <sub>8</sub> /NC	0.1-3.0	0.1 A g <sup>-1</sup>	92 (after 300 cycles)	405.2 at 0.1 A g <sup>-1</sup> 347.8 at 1 A g <sup>-1</sup>	5
SnS <sub>2</sub> /FeS <sub>2</sub> /rGO	0.01-3.0	1 A g <sup>-1</sup>	85.7 (after 500 cycles)	682.8 at 0.2 A g <sup>-1</sup> 449.7 at 1 A g <sup>-1</sup>	6
MnS-FeS <sub>2</sub> @NSC	0.01-3.0	0.1 A g <sup>-1</sup>	80.1 (after 800 cycles)	342.7 at 0.2 A g <sup>-1</sup> 266.6 at 1 A g <sup>-1</sup>	7
Cu-CoS <sub>2</sub> @Cu <sub>x</sub> S	0.4-2.6	0.3 A g <sup>-1</sup>	76 (after 300cycles)	446 at 0.2 A g <sup>-1</sup> 368 at 1 A g <sup>-1</sup>	8

SnS <sub>2</sub> -CoS <sub>2</sub> @C	0.01-2.5	0.1 A g <sup>-1</sup>	99 (after 70 cycles)	625 at 0.1 A g <sup>-1</sup> 425.1 at 1.0 A g <sup>-1</sup>	9
FeS <sub>2</sub> /MoS <sub>2</sub> -rGO	0.01-3.0	0.1 A g <sup>-1</sup>	90.1 (after 150 cycles)	432.5 at 0.1 A g <sup>-1</sup> 406 at 1 A g <sup>-1</sup>	10
Fe <sub>1-x</sub> S/MnS	0.01-2.5	0.1A g <sup>-1</sup>	81.4 (after 100 cycles)	561 at 0.05 A g <sup>-1</sup> 350 at 1 A g <sup>-1</sup>	11
CuS/FeS <sub>2</sub> @NC	0.01-3.0	0.2A g <sup>-1</sup>	99.1 (after 300 cycles)	575 at 1 A g <sup>-1</sup> 608 at 0.2 A g <sup>-1</sup>	12
Cu <sub>1.96</sub> S/NiS@DC	0.01-3.0	0.2 A g <sup>-1</sup>	95.8 (after 140 cycles)	546.5 at 0.2 A g <sup>-1</sup>	This work
		1.0 A g <sup>-1</sup>	89.1 (after 1000 cycles)	466.0 at 1 A g <sup>-1</sup>	

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Table S3 Fitting parameters of Cu<sub>1.96</sub>S/NiS@DC charged to 2.0 V in the 1st cycle.

Electrolyte	$R_e$	8.865 $\Omega$
SEI	$R_{sf}$	12.98 $\Omega$
	$CPE_{sf-T}$	6.769E-5
	$CPE_{sf-P}$	0.7561
Charge transfer	$R_{ct}$	42.1 $\Omega$
	$CPE_{ct-T}$	7.119E-5
	$CPE_{ct-P}$	0.6162
Diffusion	$R_d$ of $W_{dif}$	406.8 $\Omega$
	$T$ of $W_{dif}$	2.156
	$P$ of $W_{dif}$	1.237



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